

FIG. 1

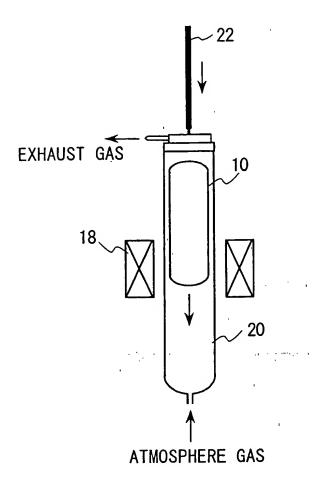


FIG. 2

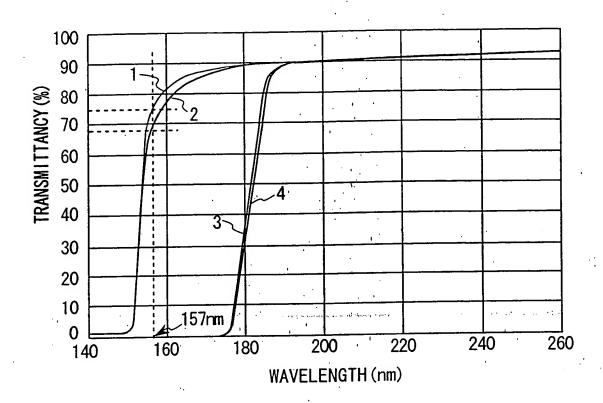


FIG. 3

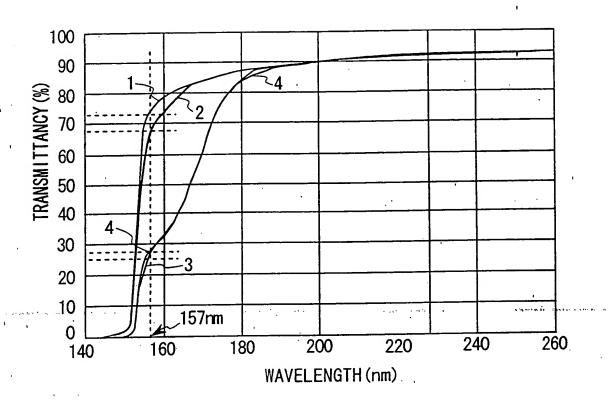


FIG. 4

		CONDITIONS	SNO	PEMARKS
		FIRST PROCESS	SECOND PROCESS	
	ATMOSPHERE	He 3 g/min, H2 0.5 g/min	SiF4 1.62/min	DDE_HEAT!NG
EXAMPLE 1	TEMPERATURE	1000°C	1380°C	PROCESS WITH H
	PASS ING SPEED	3mm/min	3mm/min	
	ATMOSPHERE		SiF4 1.62/min	
COMPARALIVE	TEMPERATURE	NONE	1380°C	NO PRE-HEATING
בVAMPLE 1	PASSING SPEED		3mm/min	
TVI TAGAGIIOO	ATMOSPHERE		SiF4 1.62/min, H2 0.52/min	NO PRE-HEATING:
CUMPAKAI I VE	TEMPERATURE	NONE	1380°C	SINTERING WITH H2
רעאוווו רר 7	PASSING SPEED		3mm/min	
ļ	ATMOSPHERE	He 32/min, Cl2 0.32/min SiF4 1.62/min,	SiF4 1.6 ε/min, H2 0.5 ε/min	DEHYDRATION
COMPAKALIVE EVANDIE 2	TEMPERATURE 1000°C	1000°C	1380°C	WITH CL2;
EVAMILLE 3	PASSING SPEED 3mm/min	3mm/min	3mm∕min	SINTERING WITH H2

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		CONDITIONS	ONS -	DEMADKS
		FIRST PROCESS	SECOND PROCESS	KLIIKANAS
	ATMOSPHERE	He 3½/min, 02 1½/min	SiF4 1.62/min	ONI TATIL TOO
EXAMPLE 2	TEMPERATURE	1000°C	1380°C	PRE-HEALING DROCESS WITH ON
	PASSING SPEED	3mm/min	3mm/min	1 NOCE 33 11 11 02
1	ATMOSPHERE		SiF4 1.62/min	
COMPAKA! IVE	TEMPERATURE	NONE	1380°C	NO PRE-HEATING
EAAMITLE 4	PASSING SPEED		3m√min	
	ATMOSPHERE		SiF4 1.62/min, 02 12/min	NO DRE-HEATING.
CUMPAKAI I VE	TEMPERATURE	NONE	1380°C	SINTERING WITH 02
	PASSING SPEED	•	3mn/min	
	ATMOSPHERE	He 31/min, Cl2 0.31/min	SiF4 1.62/min, 02 12/min	DEHYDRATION
COMPARATIVE	TEMPERATURE 1000°C	1000°C	1380°C	WITH GI2:
EXAMPLE 0	PASSING SPEED 3mm/mi	3mm/min	3mm∕min	SINTERING-WITH 02

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